

XA-7889A Re
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

Kenji NISHI

Appln. No.: 08/994,758

Group Art Unit: 2851

Filed: December 19, 1997

Examiner: A. Mathews

For: PROJECTION EXPOSURE APPARATUS



9/13
Slange
8/4/99

* * *

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action mailed January 25, 1999, please amend the above-identified patent application as indicated below.

IN THE CLAIMS:

- 1 9. (Amended) A scanning exposure apparatus
2 comprising:
3 a scanning system for synchronously scanning a mask and
4 a photosensitive substrate at respective speeds which are
5 different from each other for scanning exposure; and
6 an adjusting system for moving the mask to decrease a
7 positional deviation between the mask and the substrate,
8 independently of scanning of the mask which is performed by
9 said scanning system, during the scanning exposure.

RECEIVED
JUL 28 1999
TC 2800 MAIL ROOM

B